



Lithium lanthanum titanate thin films prepared through polymeric precursor method

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Abstract – $\text{La}_{0.50}\text{Li}_{0.50}\text{TiO}_3$ thin films were prepared by spin coating method using a polymeric organic solution. The films were deposited on Si (100) substrates and thermally treated from 400°C to 700°C for 3 h in order to study the influence of the thermal treatment temperature on the crystallinity, microstructure, grain size and roughness of the final film. X-ray diffraction (XRD) results showed that the films are polycrystalline and a secondary phase was observed (Fig.1). The thickness of films was determined by scanning electron microscopy (SEM) (Fig.2). The film surface morphology was observed with an atomic force microscope (AFM).

Lithium-conducting materials are of great interest due to their potential use as electrolytes or electrode materials in electrochemical devices such as sensors, rechargeable batteries and miniature supercapacitors [1]. Li-batteries also hold promise for the development of small capacity energy sources, which are in high demand for applications in consumer electronics [2]. The thin film battery is a promising alternative micropower source, which can be miniaturized by a typical thin film process. Discovery of high Li-ion conductivity in lithium lanthanum titanate (LLTO) has generated new interest in this direction [3].

$\text{La}_{0.50}\text{Li}_{0.50}\text{TiO}_3$ precursor solution was prepared by polymeric precursor method. This method is based on metallic citrate polymerization with use of ethylene glycol. LLTO films with 5 layers were deposited on Si (100) substrates by spin coating method at a rotation speed of 5000 rpm for 30 s. Then, the thin films were thermally treated using a two-step heat treatment. A preheating at 300°C for 1 h with heating rate of 3°C /min was used to eliminate water and excess ethylene glycol, and promote the polyesterification process. After that, the films were heated from 400°C to 700°C for 3 h with heating rate of 5°C /min to reach the crystallization stage. The crystallization process of the prepared films was analyzed by X-ray diffraction (XRD). A correlation between the process of phase crystallization and organic fraction elimination was evident. Heating the thin film at 700°C leads to a crystallization of LLTO phase and a secondary phase ($2\theta = 18.5^\circ$ and 43.5°), identified as $\text{Li}_2\text{Ti}_2\text{O}_5$. Average grain size and surface roughness of the LLTO thin films were estimated using a contact mode atomic force microscopy (AFM). The microstructure study revealed that all surfaces are not only crack-free but also appear relatively smooth. At 700°C, the beginning of the crystallization process is observed, which is followed by the growth of grains with size between 0.5 and 0.8 μm . To determine the thickness of LLTO thin films, high-magnification SEM observation was performed. It can be seen that the thickness of the films decreased with increasing the annealing temperature, between 400 and 500°C, due to the densification of films. However, as the temperature increased from 500 to 700°C, both thickness and roughness data of films increased.

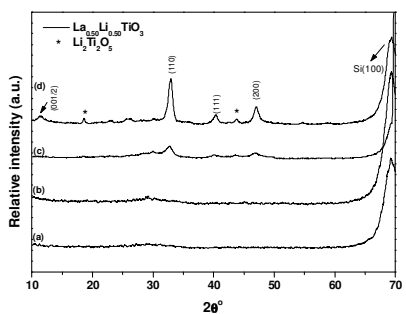


Figure 1: XRD patterns of LLTO thin films deposited on Si (100) and thermally treated at: (a) 400; (b) 500; (c) 600 and (d) 700°C/3h.

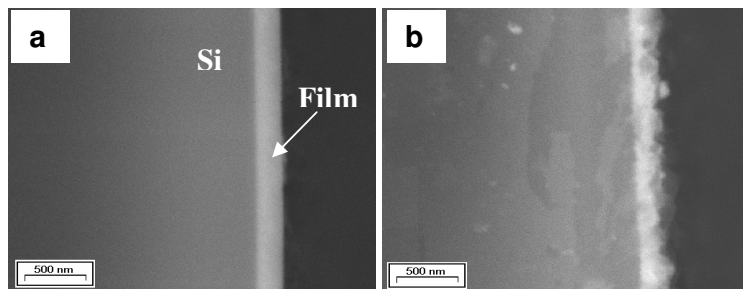


Figure 2: Thickness micrographs obtained by SEM of 5-layered $\text{La}_{0.50}\text{Li}_{0.50}\text{TiO}_3$ thin films deposited on silicon (100), and thermally treated at: (a) 400°C/3h; (b) 700°C/3h.

References

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